What is claimed is:

1. An aligner comprising a base for resting a to-be-exposed substrate thereon and a sucking unit for sucking the to-be-exposed substrate on said base, said sucking unit being capable of sucking the to-be-exposed substrate only at a part thereof.

2. An aligner according to claim 1, wherein said aligner is capable of partly exposing the to-be-exposed substrate to light, said sucking unit being capable of sucking the to-be-exposed substrate only at a part for exposure to light.

3. An aligner comprising:

a base for resting a to-be-exposed substrate thereon;

a photomask having a predetermined pattern for projection onto the to-be-exposed substrate on said base and to be contacted with or proximate to the to-be-exposed substrate;

a moving unit for moving at least one of said photomask and said base to change and set a relative positional relationship of the both;

a light source unit for radiating light for projection of the pattern of said photomask onto the to-be-exposed substrate on said base;

an aligning unit for aligning the photomask and the to-be-exposed substrate in an arbitrary area of the to-be-exposed substrate;

a sucking unit for sucking the to-be-exposed substrate at each area corresponding to the arbitrary area on said base; and

a control unit for controlling said moving unit, said aligning unit and

said light source unit such that the to-be-exposed substrate is sucked at each of the areas on said base and, after alignment, exposed to light.

4. An aligner according to claim 3, wherein the photomask is positioned vertically above the to-be-exposed substrate.

5. An aligner according to claim 3, wherein the photomask and the to-be-exposed substrate are positioned with a spacing nearly in a horizontal direction.

6. An aligner comprising:

a base for resting a to-be-exposed substrate thereon;

a photomask having a predetermined pattern for projection onto the to-be-exposed substrate on said base and to be contacted with the to-be-exposed substrate;

a moving unit for moving at least one of said photomask and said base to change and set a relative positional relationship of the both;

a light source unit for radiating light for projection of the pattern of the photomask contacting the to-be-exposed substrate onto the to-be-exposed substrate;

an aligning unit for aligning such that the photomask is to contact an arbitrary area of the to-be-exposed substrate;

a sucking unit for sucking only the area of the to-be-exposed substrate to be contacted by the photomask onto said base;

a control unit for controlling said moving unit, said aligning unit and

said light source unit such that the to-be-exposed substrate at each of the area is sucked on said base and, after alignment, exposed to light.

7. An aligner according to claim 6, wherein the photomask is positioned vertically above the to-be-exposed substrate.

8. An aligner according to claim 6, wherein the photomask and the to-be-exposed substrate are positioned with a spacing nearly in a horizontal direction.